

Form PTO-1449 (modified)		Atty. Docket No. 2008.006382	Serial N. Unknown 10/681926
List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Applicants Dinesh Chopra	
		Filing Date: 10/9/03 Concurrently Herewith	Group: 2822 2813
U.S. Patent Documents See Page 1	Foreign Patent Documents See Page 1	Other Art See Page 1	

U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
TN	A1	6,046,108	4/04/00	Liu <i>et al.</i>	438	687	
	A2	6,117,770	9/12/00	Pramanick <i>et al.</i>	438	659	
	A3	6,268,291 B1	7/31/01	Andricacos <i>et al.</i>	438	694	
	A4	6,281,127 B1	8/28/01	Shue	438	691	
	A5	6,426,289 B1	7/30/02	Farrar	438	670	
TN	A6	6,500,749 B1	12/31/02	Liu <i>et al.</i>	438	618	3/19/01

Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
TN	B1	JP10041298A	2/13/98	Japan	H01L	021/3205	Abstract only
	B2						
	B3						

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
TN	C1	Shibata <i>et al.</i> , "Lithography-less Ion Implantation Technology for Agile Fab," ULVAC Confidential
TN	C2	Shibata <i>et al.</i> , "Stencil Mask Ion Implantation Technology for High Performance MOSFETs," 2000 IEEE
	C3	

EXAMINER:

DATE CONSIDERED:

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